

Study of Structural and Optical Properties of Electrodeposited Silicon Films on Graphite Substrates

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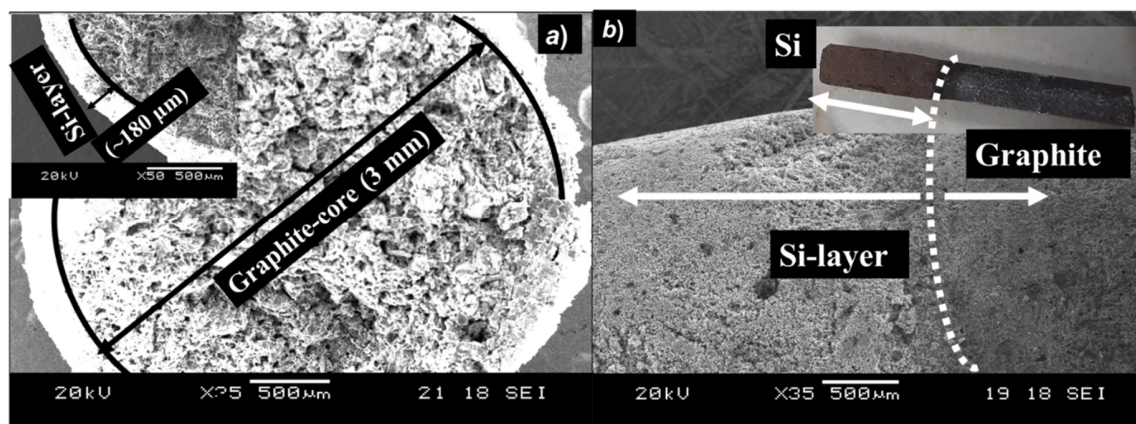


Figure S1. (a) Cross-sectional SEM image of the Si-coated graphite rod after electrochemical reduction of nano SiO_2 at low potential and washed with HCL, (b) SEM image of the electrodeposited Si-layer of the similar sample, an optical image of which has been shown at the inset of b).